

VE 320 – Summer 2012 Introduction to Semiconductor Device

Schottky Diode

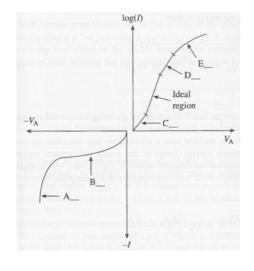
Instructor: Professor Hua Bao

NANO ENERGY LAB

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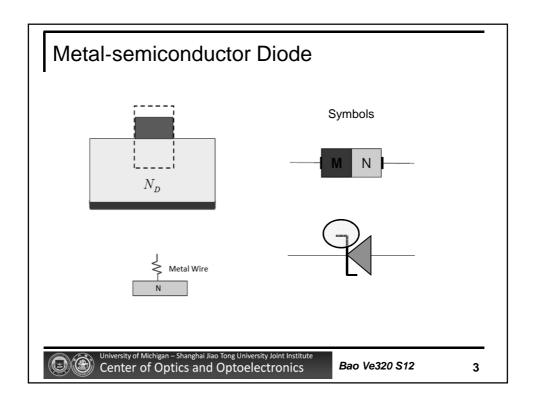
PN Junction Diode, non-ideal

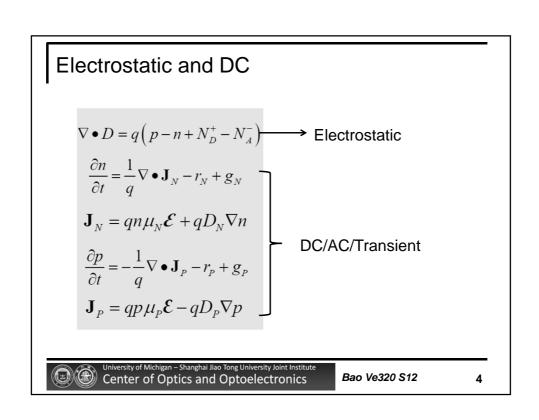


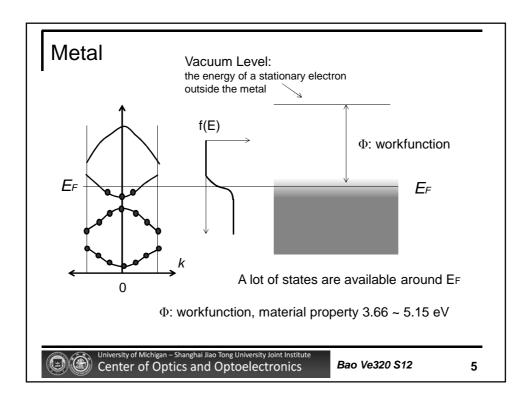
- 1. Photogeneration
- 2. Thermal recombination in the depletion region
- Avalanching and/or Zener process
- 4. Low-level injection
- 5. Depletion approximation
- Thermal generation in the depletion region
- 7. Band bending
- 8. Series resistance
- 9. $V_{\rm A} > V_{\rm bi}$
- 10. High-level injection

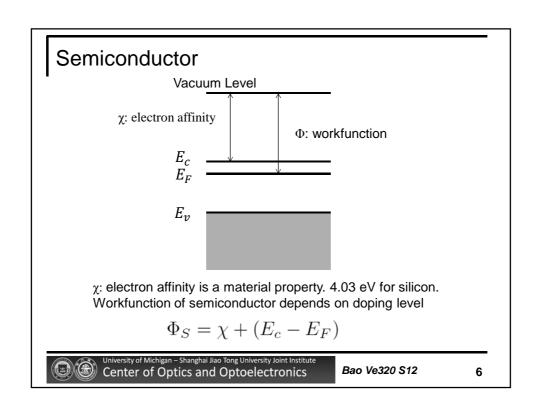
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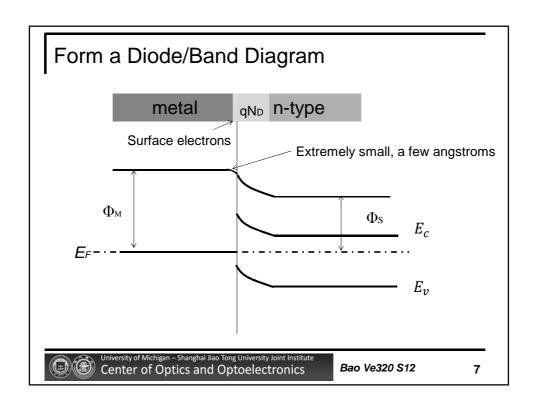
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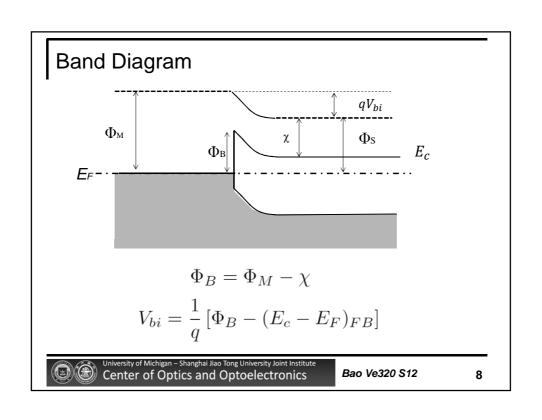


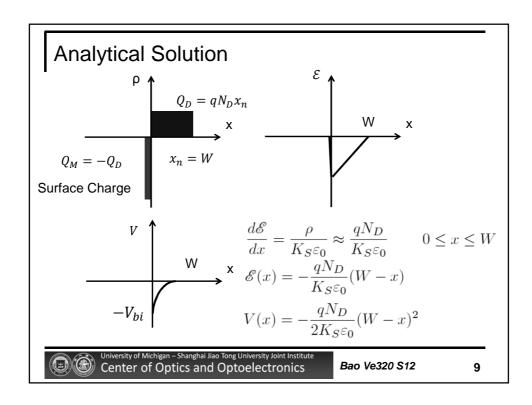


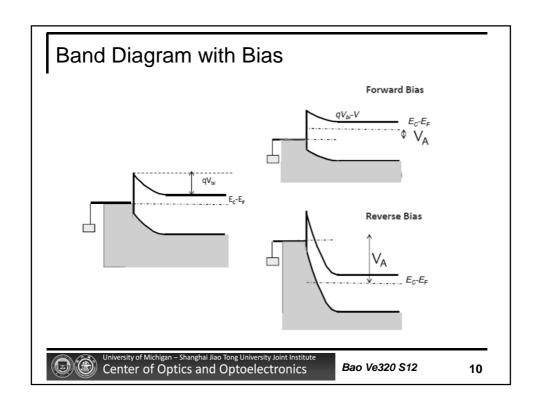












Depletion Width

metal _{qND} n-type

← W

Depletion width varies with the applied potential VA

$$-(V_{bi} - V_A) = -\frac{qN_D}{2K_S\varepsilon_0}W^2$$

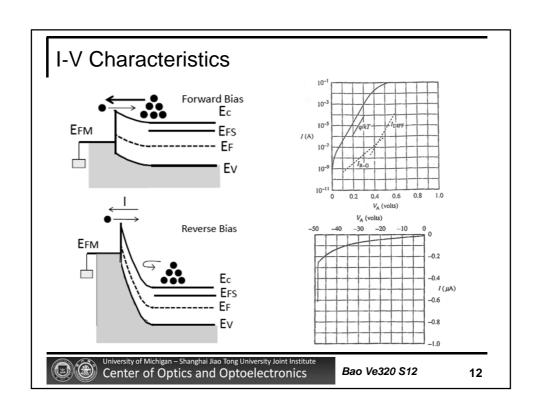
$$W = \left[\frac{2K_S\varepsilon_0}{qN_D}(V_{bi} - V_A)\right]^{1/2}$$

This solution is similar to a $p^+ - n$ junction

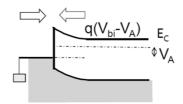
$$W = \sqrt{\frac{2K_s\varepsilon_0}{q} \left(\frac{N_A + N_D}{N_A N_D}\right) (V_{bi} - V_A)}$$

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Simple Approach



$$J_T(V_A) = J_{m \to s}(V_A) - J_{s \to m}(V_A)$$
$$= J_{m \to s}(0) - J_{s \to m}(V_A)$$

$$\begin{split} J_T(V_{\scriptscriptstyle A}=0) &= 0 = J_{\scriptscriptstyle m\to s}(0) - J_{\scriptscriptstyle s\to m}(0) \\ \Rightarrow J_{\scriptscriptstyle m\to s}(0) &= J_{\scriptscriptstyle s\to m}(0) \end{split} \tag{detailed balance}$$

$$J_T(V_A) = J_{s \to m}(0) - J_{s \to m}(V_A)$$

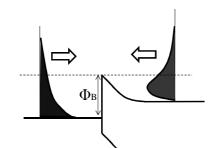
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Semiconductor to Metal Flux

$$J_{m\to s}(V_A) = -q\frac{n_m}{2}e^{-\frac{q\Phi_B}{kT}}\upsilon_{th} \qquad J_{s\to m}(V_A) = -q\frac{n_s}{2}e^{-q\frac{V_{bl}-V_A}{kT}}\upsilon_{th}$$

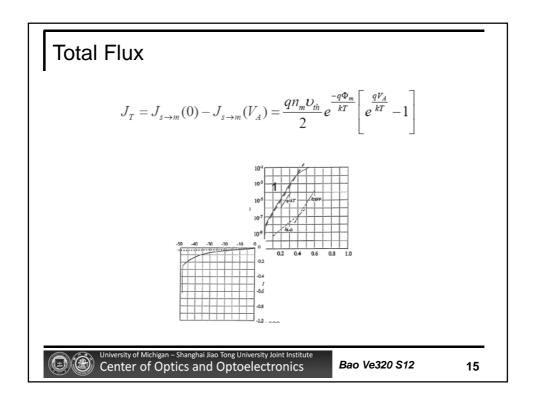


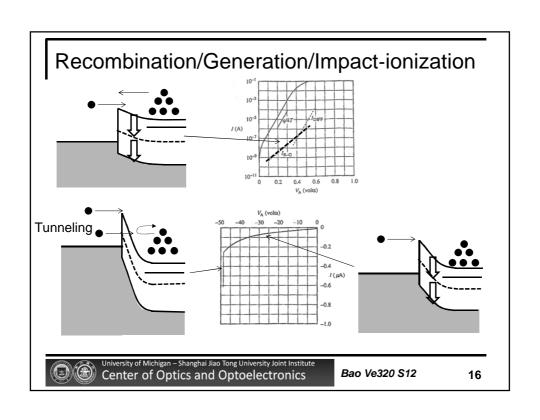
$$= -q \frac{n_s \upsilon_{th}}{2} e^{-\frac{q \upsilon_{bi}}{kT}} \times e^{\frac{q \upsilon_A}{kT}}$$
$$= -q \frac{n_m \upsilon_{th}}{2} e^{-\frac{q \upsilon_B}{kT}} e^{\frac{q \upsilon_A}{kT}}$$

$$=-q\frac{n_{m}\nu_{th}}{2}e^{-\frac{q\Phi_{B}}{kT}}e^{\frac{qV_{A}}{kT}}$$

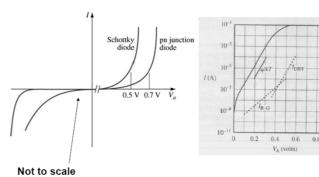
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Comparing to PN Junction Diode



- smaller Vbi
- faster in charging/discharging during transient as no accumulation of minority carrier necessary
- no high-level injection problem
- ideality factor close to 1 (ideal case)
- · lower breakdown voltage

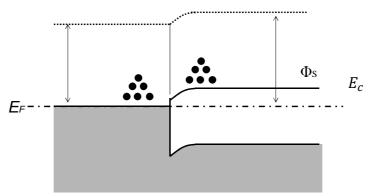


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Ohmic Contact

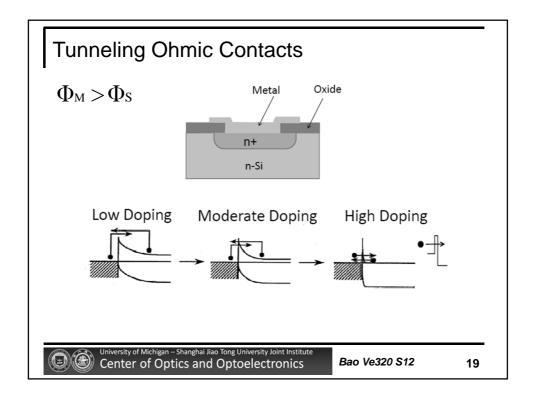
We have assumed $\Phi_{\scriptscriptstyle M} \! > \! \Phi_{\scriptscriptstyle S},$ what happens if $\Phi_{\scriptscriptstyle M} \! < \! \Phi_{\scriptscriptstyle S}$



No barrier from semiconductor to metal. Small barrier vanishes with even relatively small reverse bias. This is non-rectifying or ohmic-like.



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Summary

- M-S contact can be rectifying or ohmic-like.
- M-S diode electrostatics is similar to a p-n junction diode with one-side heavy doping.



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